

	39	(resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) with ((reduc\$5 chemical-reduc\$5 chemically-reduc\$5 chemical\$3 adj reduc\$5) near2 (plasma gas)) with (treat\$3 treatment)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 14:34
	9436	etch\$5 with (passivat\$5 ((so2 "so.sub.2" sulfur adj dioxide) with (o2 "o.sub.2" oxygen)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 14:44
	15672	((reduc\$5 chemical-reduc\$5 chemically-reduc\$5 chemical\$3 adj reduc\$5) near2 (plasma gas)) with (h2 "h.sub.2" hydrogen nh3 "nh.sub.3" ammonia hydrogen-generat\$5 h2-generat\$5 h-generat\$5 "h.sub.2"-generat\$5)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 15:23
	0	(resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) same (etch\$5 with (passivat\$5 ((so2 "so.sub.2" sulfur adj dioxide) with (o2 "o.sub.2" oxygen))) same (((reduc\$5 chemical-reduc\$5 chemically-reduc\$5 chemical\$3 adj reduc\$5) near2 (plasma gas)) with (h2 "h.sub.2" hydrogen nh3 "nh.sub.3" ammonia hydrogen-generat\$5 h2-generat\$5 h-generat\$5 "h.sub.2"-generat\$5))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 14:46
	4	(etch\$5 with (passivat\$5 ((so2 "so.sub.2" sulfur adj dioxide) with (o2 "o.sub.2" oxygen))) same (((reduc\$5 chemical-reduc\$5 chemically-reduc\$5 chemical\$3 adj reduc\$5) near2 (plasma gas)) with (h2 "h.sub.2" hydrogen nh3 "nh.sub.3" ammonia hydrogen-generat\$5 h2-generat\$5 h-generat\$5 "h.sub.2"-generat\$5))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 14:43
	10866	(plasma gas) with (passivat\$5 ((so2 "so.sub.2" sulfur adj dioxide) with (o2 "o.sub.2" oxygen)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 14:52
	590	(resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) same (etch\$5 with (passivat\$5 ((so2 "so.sub.2" sulfur adj dioxide) with (o2 "o.sub.2" oxygen))) same ((plasma gas) with (passivat\$5 ((so2 "so.sub.2" sulfur adj dioxide) with (o2 "o.sub.2" oxygen))))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 14:46
	334	(resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) with (etch\$5 with (passivat\$5 ((so2 "so.sub.2" sulfur adj dioxide) with (o2 "o.sub.2" oxygen))) with ((plasma gas) with (passivat\$5 ((so2 "so.sub.2" sulfur adj dioxide) with (o2 "o.sub.2" oxygen))))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 14:51
	5972	(resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) near2 oxide	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 14:51

	9	((resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) same (etch\$5 with (passivat\$5 ((so2 "so.sub.2" sulfur adj dioxide) with (o2 "o.sub.2" oxygen)))) same ((plasma gas) with (passivat\$5 ((so2 "so.sub.2" sulfur adj dioxide) with (o2 "o.sub.2" oxygen)))) same ((resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) near2 oxide) (plasma gas) with (passivat\$5 ((so2 "so.sub.2" sulfur adj dioxide) with (o2 "o.sub.2" oxygen))) with (etch\$5 transfer\$5 pattern\$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 14:51
	1989		USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 14:53
	0	((resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) with (((reduc\$5 chemical-reduc\$5 chemically-reduc\$5 chemical\$3 adj reduc\$5) near2 (plasma gas)) with (h2 "h.sub.2" hydrogen nh3 "nh.sub.3" ammonia hydrogen-generat\$5 h2-generat\$5 h-generat\$5 "h.sub.2"-generat\$5)) with ((plasma gas) with (passivat\$5 ((so2 "so.sub.2" sulfur adj dioxide) with (o2 "o.sub.2" oxygen))) with (etch\$5 transfer\$5 pattern\$3))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 14:54
	0	((resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) same (((reduc\$5 chemical-reduc\$5 chemically-reduc\$5 chemical\$3 adj reduc\$5) near2 (plasma gas)) with (h2 "h.sub.2" hydrogen nh3 "nh.sub.3" ammonia hydrogen-generat\$5 h2-generat\$5 h-generat\$5 "h.sub.2"-generat\$5)) same ((plasma gas) with (passivat\$5 ((so2 "so.sub.2" sulfur adj dioxide) with (o2 "o.sub.2" oxygen))) with (etch\$5 transfer\$5 pattern\$3))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 14:54
	7	(((reduc\$5 chemical-reduc\$5 chemically-reduc\$5 chemical\$3 adj reduc\$5) near2 (plasma gas)) with (h2 "h.sub.2" hydrogen nh3 "nh.sub.3" ammonia hydrogen-generat\$5 h2-generat\$5 h-generat\$5 "h.sub.2"-generat\$5)) same ((plasma gas) with (passivat\$5 ((so2 "so.sub.2" sulfur adj dioxide) with (o2 "o.sub.2" oxygen))) with (etch\$5 transfer\$5 pattern\$3))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 14:54
	20	((resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) and (((reduc\$5 chemical-reduc\$5 chemically-reduc\$5 chemical\$3 adj reduc\$5) near2 (plasma gas)) with (h2 "h.sub.2" hydrogen nh3 "nh.sub.3" ammonia hydrogen-generat\$5 h2-generat\$5 h-generat\$5 "h.sub.2"-generat\$5)) and ((plasma gas) with (passivat\$5 ((so2 "so.sub.2" sulfur adj dioxide) with (o2 "o.sub.2" oxygen))) with (etch\$5 transfer\$5 pattern\$3))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 15:00
	2	(stabiliz\$5 with high with aspect with ratio) same ((reduc\$5 chemical-reduc\$5 chemically-reduc\$5 chemical\$3 adj reduc\$5) near2 (plasma gas))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 15:00

	79	stabiliz\$5 with high with aspect with ratio	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 15:00
	2	(resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) with ((reduc\$5 chemical-reduc\$5 chemically-reduc\$5 chemical\$3 adj reduc\$5) near2 (plasma gas)) with (stabiliz\$5 with high with aspect with ratio)	USPAT; US-PGPUB; EPO; JPO; DERWENT)	2004/03/02 15:04
	2	(resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) same ((reduc\$5 chemical-reduc\$5 chemically-reduc\$5 chemical\$3 adj reduc\$5) near2 (plasma gas)) same (stabiliz\$5 with high with aspect with ratio)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 15:05
	8529	430/311,313,314,316,317.ccls. 438/710.ccls. 216/67.ccls. 134/1.2.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 15:05
	616	((reduc\$5 chemical-reduc\$5 chemically-reduc\$5 chemical\$3 adj reduc\$5) near2 (plasma gas)) and (430/311,313,314,316,317.ccls. 438/710.ccls. 216/67.ccls. 134/1.2.ccls.)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 15:06
	152	((chemical-reduc\$5 chemically-reduc\$5 chemical\$3 adj reduc\$5) near2 (plasma gas))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 15:17
	2	(resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) with ((chemical-reduc\$5 chemically-reduc\$5 chemical\$3 adj reduc\$5) near2 (plasma gas))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 15:09
	2	(resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) same ((chemical-reduc\$5 chemically-reduc\$5 chemical\$3 adj reduc\$5) near2 (plasma gas))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 15:09
	19	((resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) 430/\$.ccls.) and ((chemical-reduc\$5 chemically-reduc\$5 chemical\$3 adj reduc\$5) near2 (plasma gas))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 15:10
	56381	((reduc\$5) near (plasma gas))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 15:22
	222	(resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) with ((reduc\$5) near (plasma gas))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 15:22
	1412666	(h2 "h.sub.2" hydrogen nh3 ethylene c2h4 "c.sub.2 h.sub.4" hydrogen-generat\$5 h2-generat\$5 h-generat\$5 "h.sub.2"-generat\$5)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 16:39
	34	((resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) with ((reduc\$5) near (plasma gas))) with ((h2 "h.sub.2" hydrogen nh3 ethylene c2h4 "c.sub.2 h.sub.4" hydrogen-generat\$5 h2-generat\$5 h-generat\$5 "h.sub.2"-generat\$5))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 15:34

	435139	(polymer polymeric organic novolac novolak low-k adj dielectric silk) near (layer film coating underlayer material under-layer under adj layer) 2 ((polymer polymeric organic novolac novolak low-k adj dielectric silk) near (layer film coating underlayer material under-layer under adj layer)) with ((chemical-reduc\$5 chemically-reduc\$5 chemical\$3 adj reduc\$5) near2 (plasma gas)) 6 ((polymer polymeric organic novolac novolak low-k adj dielectric silk) near (layer film coating underlayer material under-layer under adj layer)) same ((chemical-reduc\$5 chemically-reduc\$5 chemical\$3 adj reduc\$5) near2 (plasma gas))	USPAT; US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 15:35 2004/03/02 15:46 2004/03/02 15:41
	88530	(h2 "h.sub.2" hydrogen nh3 ethylene c2h4 "c.sub.2 h.sub.4" hydrogen-generat\$5 h2-generat\$5 h-generat\$5 "h.sub.2"-generat\$5) near (plasma gas) ((polymer polymeric organic novolac novolak low-k adj dielectric silk) near (layer film coating underlayer material under-layer under adj layer)) with ((h2 "h.sub.2" hydrogen nh3 ethylene c2h4 "c.sub.2 h.sub.4" hydrogen-generat\$5 h2-generat\$5 h-generat\$5 "h.sub.2"-generat\$5) near (plasma gas))	USPAT; US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 15:45 2004/03/02 15:49
	299	((polymer polymeric organic novolac novolak low-k adj dielectric silk) near (layer film coating underlayer material under-layer under adj layer)) with ((h2 "h.sub.2" hydrogen nh3 ethylene c2h4 "c.sub.2 h.sub.4" hydrogen-generat\$5 h2-generat\$5 h-generat\$5 "h.sub.2"-generat\$5) near (plasma gas))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 15:46
	19	((polymer polymeric organic novolac novolak low-k adj dielectric silk) near (layer film coating underlayer material under-layer under adj layer)) with ((h2 "h.sub.2" hydrogen nh3 ethylene c2h4 "c.sub.2 h.sub.4" hydrogen-generat\$5 h2-generat\$5 h-generat\$5 "h.sub.2"-generat\$5) near (plasma gas)) with (resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 15:49
	160	((polymer polymeric organic novolac novolak low-k adj dielectric silk) near (layer film coating underlayer material under-layer under adj layer)) with ((reduc\$5) near (plasma gas))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 15:49
	10	((polymer polymeric organic novolac novolak low-k adj dielectric silk) near (layer film coating underlayer material under-layer under adj layer)) with ((reduc\$5) near (plasma gas)) with (resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 15:49
	11	((("5985524") or ("20030017420") or ("20030017711") or ("6528432") or ("5833758") or ("6465159") or ("6562700") or ("4904866") or ("5688719") or ("6261951") or ("6444408")).PN.	USPAT; US-PGPUB	2004/03/02 15:57
	12	((("5985524") or ("6218085") or ("6503840") or ("6673721") or ("6562700") or ("6420098") or ("6225219") or ("6528432") or ("5833758") or ("6465159") or ("6562700") or ("4904866") or ("5688719")).PN.	USPAT; US-PGPUB	2004/03/02 15:54
	4	ep-903777-\$.did. jp-2000200832-\$.did.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 15:57

-	20	(ep-903777-\$ did. jp-2000200832-\$ did.) (((5985524") or ("20030017420") or ("20030017711") or ("6528432") or ("5833758") or ("6465159") or ("6562700") or ("4904866") or ("5688719") or ("6261951") or ("6444408")).PN.) (((5985524") or ("6218085") or ("6503840") or ("6673721") or ("6562700") or ("6420098") or ("6225219") or ("6528432") or ("5833758") or ("6465159") or ("6562700") or ("4904866") or ("5688719")).PN.)	USPAT; US-PPGPUB; EPO; JPO; DERWENT	2004/03/02 15:57
-	10	((ep-903777-\$ did. jp-2000200832-\$ did.) (((5985524") or ("20030017420") or ("20030017711") or ("6528432") or ("5833758") or ("6465159") or ("6562700") or ("4904866") or ("5688719") or ("6261951") or ("6444408")).PN.) (((5985524") or ("6218085") or ("6503840") or ("6673721") or ("6562700") or ("6420098") or ("6225219") or ("6528432") or ("5833758") or ("6465159") or ("6562700") or ("4904866") or ("5688719")).PN.)) and (((reduc\$5 chemical-reduc\$5 chemically-reduc\$5 chemical\$3 adj reduc\$5) near2 (plasma gas)) (stabiliz\$5 with high with aspect with ratio))	USPAT; US-PPGPUB; EPO; JPO; DERWENT	2004/03/02 16:06
-	10	((ep-903777-\$ did. jp-2000200832-\$ did.) (((5985524") or ("20030017420") or ("20030017711") or ("6528432") or ("5833758") or ("6465159") or ("6562700") or ("4904866") or ("5688719") or ("6261951") or ("6444408")).PN.) (((5985524") or ("6218085") or ("6503840") or ("6673721") or ("6562700") or ("6420098") or ("6225219") or ("6528432") or ("5833758") or ("6465159") or ("6562700") or ("4904866") or ("5688719")).PN.)) not ((ep-903777-\$ did. jp-2000200832-\$ did.) (((5985524") or ("20030017420") or ("20030017711") or ("6528432") or ("5833758") or ("6465159") or ("6562700") or ("4904866") or ("5688719") or ("6261951") or ("6444408")).PN.) (((5985524") or ("6218085") or ("6503840") or ("6673721") or ("6562700") or ("6420098") or ("6225219") or ("6528432") or ("5833758") or ("6465159") or ("6562700") or ("4904866") or ("5688719")).PN.)) and (((reduc\$5 chemical-reduc\$5 chemically-reduc\$5 chemical\$3 adj reduc\$5) near2 (plasma gas)) (stabiliz\$5 with high with aspect with ratio)))	USPAT; US-PPGPUB; EPO; JPO; DERWENT	2004/03/02 16:27
-	2	("6114259").PN.	USPAT; US-PPGPUB; EPO; JPO; DERWENT	2004/03/02 16:27
-	36510	((polymer polymeric organic novolac novolak low-k adj dielectric silk) near (layer film coating underlayer material under-layer under adj layer) with (stabiliz\$5 harden\$3 treat\$4)	USPAT; US-PPGPUB; EPO; JPO; DERWENT	2004/03/02 16:39
-	2545	((polymer polymeric organic novolac novolak low-k adj dielectric silk) near (layer film coating underlayer material under-layer under adj layer) with (stabiliz\$5 harden\$3 treat\$4) with (gas plasma)	USPAT; US-PPGPUB; EPO; JPO; DERWENT	2004/03/02 16:38

	5376123	(reduc\$5 chemical-reduc\$5 chemically-reduc\$5 chemical\$3 adj reduc\$5)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 16:39
	1412666	(h2 "h.sub.2" hydrogen nh3 ethylene c2h4 "c.sub.2 h.sub.4" hydrogen-generat\$5 h2-generat\$5 h-generat\$5 "h.sub.2"-generat\$5)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 16:39
	357	((polymer polymeric organic novolac novolak low-k adj dielectric silk) near (layer film coating underlayer material under-layer under adj layer)) with (stabiliz\$5 harden\$3 treat\$4) with (gas plasma) with (((reduc\$5 chemical-reduc\$5 chemically-reduc\$5 chemical\$3 adj reduc\$5)) ((h2 "h.sub.2" hydrogen nh3 ethylene c2h4 "c.sub.2 h.sub.4" hydrogen-generat\$5 h2-generat\$5 h-generat\$5 "h.sub.2"-generat\$5)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 17:08
	30	((polymer polymeric organic novolac novolak low-k adj dielectric silk) near (layer film coating underlayer material under-layer under adj layer)) with (stabiliz\$5 harden\$3 treat\$4) with (gas plasma) with (((reduc\$5 chemical-reduc\$5 chemically-reduc\$5 chemical\$3 adj reduc\$5)) with ((h2 "h.sub.2" hydrogen nh3 ethylene c2h4 "c.sub.2 h.sub.4" hydrogen-generat\$5 h2-generat\$5 h-generat\$5 "h.sub.2"-generat\$5)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 16:44
	31	((polymer polymeric organic novolac novolak low-k adj dielectric silk) near (layer film coating underlayer material under-layer under adj layer)) with (stabiliz\$5 harden\$3 treat\$4) with (gas plasma) with (((reduc\$5 chemical-reduc\$5 chemically-reduc\$5 chemical\$3 adj reduc\$5)) ((h2 "h.sub.2" hydrogen nh3 ethylene c2h4 "c.sub.2 h.sub.4" hydrogen-generat\$5 h2-generat\$5 h-generat\$5 "h.sub.2"-generat\$5))) with (resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 17:05
	28	((((polymer polymeric organic novolac novolak low-k adj dielectric silk) near (layer film coating underlayer material under-layer under adj layer)) with (stabiliz\$5 harden\$3 treat\$4) with (gas plasma) with (((reduc\$5 chemical-reduc\$5 chemically-reduc\$5 chemical\$3 adj reduc\$5)) ((h2 "h.sub.2" hydrogen nh3 ethylene c2h4 "c.sub.2 h.sub.4" hydrogen-generat\$5 h2-generat\$5 h-generat\$5 "h.sub.2"-generat\$5))) with (resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation)))) not (((polymer polymeric organic novolac novolak low-k adj dielectric silk) near (layer film coating underlayer material under-layer under adj layer)) with (stabiliz\$5 harden\$3 treat\$4) with (gas plasma) with (((reduc\$5 chemical-reduc\$5 chemically-reduc\$5 chemical\$3 adj reduc\$5)) with ((h2 "h.sub.2" hydrogen nh3 ethylene c2h4 "c.sub.2 h.sub.4" hydrogen-generat\$5 h2-generat\$5 h-generat\$5 "h.sub.2"-generat\$5))))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 17:06

	52	((((polymer polymeric organic novolac novolak low-k adj dielectric silk) near (layer film coating underlayer material under-layer under adj layer)) with (stabiliz\$5 harden\$3 treat\$4) with (gas plasma)) with (((reduc\$5 chemical-reduc\$5 chemically-reduc\$5 chemical\$3 adj reduc\$5)) ((h2 "h.sub.2" hydrogen nh3 ethylene c2h4 "c.sub.2 h.sub.4" hydrogen-generat\$5 h2-generat\$5 h-generat\$5 "h.sub.2"-generat\$5)))) and (430/\$.ccls. 438/\$.ccls.)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 17:08
	33	((((polymer polymeric organic novolac novolak low-k adj dielectric silk) near (layer film coating underlayer material under-layer under adj layer)) with (stabiliz\$5 harden\$3 treat\$4) with (gas plasma)) with (((reduc\$5 chemical-reduc\$5 chemically-reduc\$5 chemical\$3 adj reduc\$5)) ((h2 "h.sub.2" hydrogen nh3 ethylene c2h4 "c.sub.2 h.sub.4" hydrogen-generat\$5 h2-generat\$5 h-generat\$5 "h.sub.2"-generat\$5)))) and (430/\$.ccls. 438/\$.ccls.)) not (((((polymer polymeric organic novolac novolak low-k adj dielectric silk) near (layer film coating underlayer material under-layer under adj layer)) with (stabiliz\$5 harden\$3 treat\$4) with (gas plasma)) with (((reduc\$5 chemical-reduc\$5 chemically-reduc\$5 chemical\$3 adj reduc\$5)) ((h2 "h.sub.2" hydrogen nh3 ethylene c2h4 "c.sub.2 h.sub.4" hydrogen-generat\$5 h2-generat\$5 h-generat\$5 "h.sub.2"-generat\$5))) with (resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))))) not (((((polymer polymeric organic novolac novolak low-k adj dielectric silk) near (layer film coating underlayer material under-layer under adj layer)) with (stabiliz\$5 harden\$3 treat\$4) with (gas plasma)) with (((reduc\$5 chemical-reduc\$5 chemically-reduc\$5 chemical\$3 adj reduc\$5)) with ((h2 "h.sub.2" hydrogen nh3 ethylene c2h4 "c.sub.2 h.sub.4" hydrogen-generat\$5 h2-generat\$5 h-generat\$5 "h.sub.2"-generat\$5))))) (((polymer polymeric organic novolac novolak low-k adj dielectric silk) near (layer film coating underlayer material under-layer under adj layer)) with (stabiliz\$5 harden\$3 treat\$4) with (gas plasma)) with (((reduc\$5 chemical-reduc\$5 chemically-reduc\$5 chemical\$3 adj reduc\$5)) ((h2 "h.sub.2" hydrogen nh3 ethylene c2h4 "c.sub.2 h.sub.4" hydrogen-generat\$5 h2-generat\$5 h-generat\$5 "h.sub.2"-generat\$5))) with (resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation)))))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/02 17:09